

## Pressure Effect on Transport Properties of $\text{EuNi}(\text{Si}_{1-x}\text{Ge}_x)_3$ Compounds

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### Abstract

The compounds of  $\text{EuNi}(\text{Si}_{1-x}\text{Ge}_x)_3$  order antiferromagnetically. At the temperature  $T_C$  below the Néel temperature  $T_N$ ,  $\text{EuNiSi}_3$  ( $x = 0$ ) shows an additional magnetic transition into ferromagnetic state.  $T_N$  decreases monotonously with increasing the Ge composition  $x$ . The Curie temperature  $T_C$  decreases rapidly with increasing  $x$  and vanishes at the critical composition  $x \approx 0.3$ . We have measured the electrical resistivity and thermopower of  $\text{EuNi}(\text{Si}_{0.8}\text{Ge}_{0.2})_3$ , which is a compound near to the boundary between the ferromagnetic and antiferromagnetic ground states in the phase diagram for  $\text{EuNi}(\text{Si}_{1-x}\text{Ge}_x)_3$  system, under pressures up to 1.8 GPa at temperatures from 2 to 300 K. The anomalies in  $\rho(T)$  and  $S(T)$  curves of  $\text{EuNi}(\text{Si}_{0.8}\text{Ge}_{0.2})_3$  are observed at  $T_C = 16$  K and  $T_N = 34$  K at ambient pressure. Both  $T_C$  and  $T_N$  increase linearly with increasing pressure. The temperature variations of  $\rho$  and  $S$  of  $\text{EuNi}(\text{Si}_{0.8}\text{Ge}_{0.2})_3$  at  $P = 1.8$  GPa are almost the same as those of  $\text{EuNi}(\text{Si}_{0.9}\text{Ge}_{0.1})_3$  ( $x=0.1$ ) at ambient pressure, revealing that the effect of pressure on  $T_N$  and  $T_C$  is the same as that of the increase of Si concentration. The pressure and atomic composition dependences of the magnetic transition temperatures  $T_N$  and  $T_C$  can be expressed by using the Grüneisen parameters. These results indicate that the changes of  $T_N$  and  $T_C$  are attributed to the change of atomic volume induced by the applying pressure or the atomic substitution.

**Keywords:** Electrical resistivity, Thermopower, Pressure effect, Magnetic phase transition

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## 1 Introduction

In Eu compounds, it is well known to exhibit the valence instability, depending on the temperature, magnetic field, pressure and atomic composition. The accumulated data show that the stable states of  $\text{Eu}^{2+}$  ( $4f^76s^2$ ),  $\text{Eu}^{3+}$  ( $4f^65d^16s^2$ ) and dynamic intermediate valence state are possible for Eu. The electronic state of  $\text{Eu}^{2+}$  is magnetic with  $J = 7/2$  ( $S = 7/2$ ,  $L = 0$ ), which is the same as that of the corresponding Gd compound, while the  $\text{Eu}^{3+}$  state is non-magnetic with  $J = 0$  ( $S = L = 3$ ). Here,  $J$  is a total angular momentum,  $S$  is a spin angular momentum, and  $L$  is an orbital angular momentum.

In  $\text{RT}_2\text{X}_2$  with the  $\text{ThCr}_2\text{Si}_2$ -type tetragonal structure, for example,  $\text{EuNi}_2\text{Ge}_2$ , in which the Eu atoms are in the  $\text{Eu}^{2+}$  state, manifests an antiferromagnetic order at the  $T_N \approx 30$  K.  $\text{EuNi}_2\text{Si}_2$ , in which Eu atoms are in the  $\text{Eu}^{3+}$  state, is the Pauli-paramagnetism with temperature-independent magnetic susceptibility. Interestingly,  $\text{EuNi}_2\text{Ge}_2$  shows the valence transition from divalent- into trivalent-electronic states by the replacement of Ge by Si. Due to a large difference in atomic size between  $\text{Eu}^{2+}$  and  $\text{Eu}^{3+}$  ions, the Eu valence depends strongly on the change of the atomic volume induced by the atomic replacement or the applying pressure [1, 2, 3]. On the other hand,  $\text{RTX}_3$  (R=rare earth, T=transition metal, and X=Si, Ge) compounds, which crystallize in the  $\text{ThCr}_2\text{Si}_2$ -type or  $\text{BaNiSi}_3$ -type tetragonal structures [4], have been studied extensively from the scientific and practical view points. However, few studies on  $\text{EuNiX}_3$  (X=Si, Ge), as far as we know, have been reported in the literature. In our previous work [5, 6], for the  $\text{EuNi}(\text{Si}_{1-x}\text{Ge}_x)_3$  compounds, we obtained the effective magnetic moment of  $\mu_{\text{eff}} \approx 7.7 \mu_B$ , which is close to a divalent Eu value of  $\mu_{\text{eff}} = 7.94 \mu_B$ . The Néel temperature  $T_N$  decreases monotonously with increasing the Ge composition  $x$  from  $T_N = 49$  K for  $\text{EuNiSi}_3$  to  $T_N = 14$  K for  $\text{EuNiGe}_3$ . The Curie temperature  $T_C = 16$  K below  $T_N$  in  $\text{EuNiSi}_3$  decreases rapidly with increasing  $x$  and vanishes at the critical Ge composition  $x \approx 0.3$ . At the low temperatures below  $T_N$ , the anomalies corresponding to additional magnetic phase transition into another antiferromagnetic state for  $x > 0.3$  was observed [7].

In order to investigate the effect of pressure on the magnetic and transport properties of  $\text{EuNi}(\text{Si}_{1-x}\text{Ge}_x)_3$  system, we have performed the measurements of the electrical resistivity  $\rho$  and thermopower  $S$  of  $\text{EuNi}(\text{Si}_{0.8}\text{Ge}_{0.2})_3$ , which is a compound near to the boundary between the ferromagnetic and antiferromagnetic ground states in the phase diagram for  $\text{EuNi}(\text{Si}_{1-x}\text{Ge}_x)_3$  system, under pressures up to 1.8 GPa at temperatures from 2 to 300 K.

## 2 Experimental procedures

The polycrystalline samples of  $\text{EuNi}(\text{Si}_{1-x}\text{Ge}_x)_3$  compounds were prepared from the pure components of 3N(99.9 % pure)-Eu, 5N-Ni and 5N-Si(Ge) by melting in an arc-furnace under a protective Ar atmosphere and was subsequently annealed in vacuum at 800 °C for five days. It was reported that  $\text{EuNiSi}_3$  is  $\text{ThCr}_2\text{Si}_2$ -type tetragonal structure with lattice parameters of  $a = 4.158 \text{ \AA}$  and  $c = 9.636 \text{ \AA}$  [4], and  $\text{EuNiGe}_3$  is  $\text{BaNiSn}_3$ -type tetragonal structure with lattice parameters of  $a = 4.339 \text{ \AA}$  and  $c = 9.887 \text{ \AA}$  [6]. The tetragonal crystal structure have been confirmed for all compounds of  $\text{EuNi}(\text{Si}_{1-x}\text{Ge}_x)_3$  by the powder X-ray diffraction measurement.

The electrical resistivity  $\rho$  was measured by means of the standard four-probe dc method. The differential method with the seesaw-heating procedure was used for the thermopower  $S$  measurement [8]. The electrical resistivity and thermopower were measured simultaneously in the temperature range from 2 to 300 K. A clamp-type hybrid piston-cylinder-pressure-cell with Daphne oil 7373 as the pressure transmitting medium was utilized for the measurements of  $\rho$  and  $S$  under pressures up to 1.8 GPa at the temperatures from 2 to 300 K [9]. In these pressure

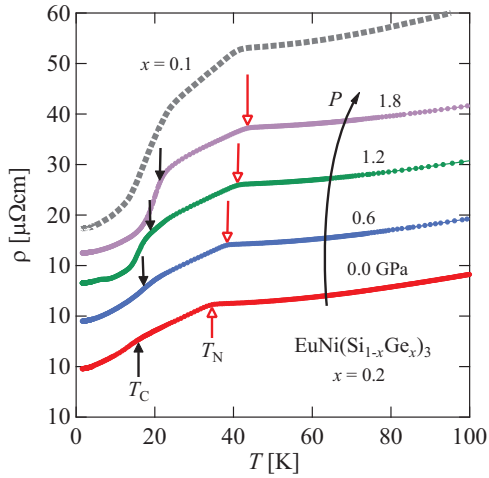


Figure 1: Temperature dependence of the electrical resistivity  $\rho$  of  $\text{EuNi}(\text{Si}_{0.8}\text{Ge}_{0.2})_3$  under pressures up to 1.8 GPa at temperatures from 2 to 100 K. The dotted line indicates  $\rho(T)$  of  $\text{EuNi}(\text{Si}_{0.9}\text{Ge}_{0.1})_3$  at ambient pressure. The data are shifted up for eyes.

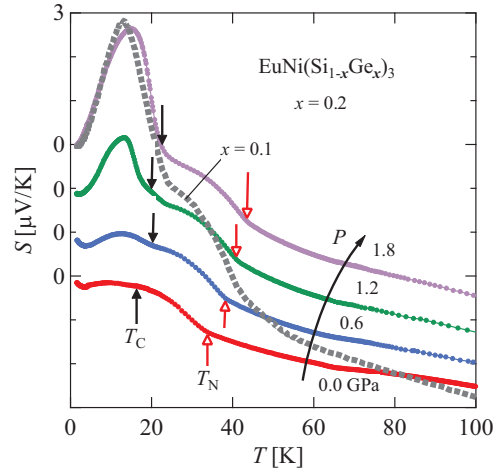


Figure 2: Temperature dependence of the thermopower  $S$  of  $\text{EuNi}(\text{Si}_{0.8}\text{Ge}_{0.2})_3$  under pressures up to 1.8 GPa at temperatures from 2 to 100 K. The dotted line indicates  $S(T)$  of  $\text{EuNi}(\text{Si}_{0.9}\text{Ge}_{0.1})_3$  at ambient pressure. The data are shifted up for eyes.

measurements, the applied pressure was estimated from the load on piston of the pressure cell at room temperature.

### 3 Results and Discussion

Figure 1 shows the temperature dependence of the electrical resistivity  $\rho$  of  $\text{EuNi}(\text{Si}_{0.8}\text{Ge}_{0.2})_3$  under pressures up to  $P = 1.8$  GPa at the temperature region from 2 to 100 K. As shown in Fig. 1,  $\rho$  increases with increasing temperature, showing anomalies in the form of kink at the magnetic transition temperatures of  $T_C \approx 16$  K and  $T_N \approx 34$  K, and shows a linear increase with further increasing temperature. Both  $T_C$  and  $T_N$ , pointed by the solid and open arrows, respectively, in Fig. 1, increase with increasing pressure. As can be seen in Fig. 1, the temperature variation of  $\rho$  of  $\text{EuNi}(\text{Si}_{0.8}\text{Ge}_{0.2})_3$  at  $P = 1.8$  GPa is very similar to that of  $\text{EuNi}(\text{Si}_{0.9}\text{Ge}_{0.1})_3$  at ambient pressure, which is indicated by the dotted line. This result reveals that the pressure effect on  $\rho$  is opposite to that of the substitution of Si by Ge in  $\text{EuNi}(\text{Si}_{1-x}\text{Ge}_x)_3$  system.

Figure 2 depicts temperature dependence of the thermopower  $S$  of  $\text{EuNi}(\text{Si}_{0.8}\text{Ge}_{0.2})_3$  under selected pressures up to 1.8 GPa. At ambient pressure,  $S$  decreases with increasing temperature, taking a minimum at  $T \approx 3.5$  K and a maximum at  $T \approx 10$  K, and shows shoulder-like behavior at  $T_C \approx 16$  K and an additional anomaly in the form of kink at  $T_N \approx 34$  K.  $S$  decreases monotonically with further increasing temperature. At the pressure of  $P \approx 1.0$  GPa, a maximum value of  $S$  at low temperature region changes its sign from negative to positive. Finally,  $S$  at  $P = 1.8$  GPa also shows almost the same temperature variation as that of  $\text{EuNi}(\text{Si}_{0.9}\text{Ge}_{0.1})_3$  at ambient pressure, indicated by the dotted line in Fig. 2. In the low-temperature limit, the

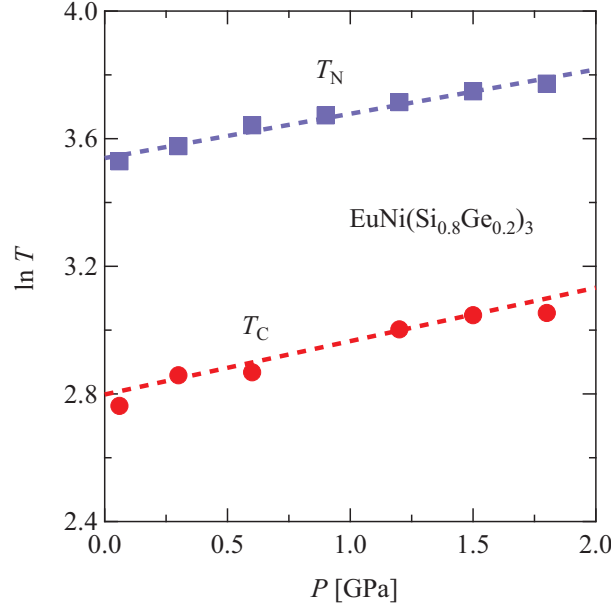


Figure 3: Pressure dependences of the magnetic transition temperatures of  $T_N$  and  $T_C$  of  $\text{EuNi}(\text{Si}_{0.8}\text{Ge}_{0.2})_3$  in the form of  $\ln T_m$  vs.  $P$ . The dashed lines are the results of the line fittings to the experimental data.

thermopower  $S$  for metallic conductor is expressed by the Mott's formula:

$$S(T) = -\frac{\pi^2 k_B^2}{3|e|} T \left( \frac{1}{\sigma} \frac{\partial \sigma}{\partial \varepsilon} \right)_{\varepsilon=\varepsilon_F},$$

where  $e$ ,  $k_B$  and  $\sigma$  are the electronic charge, the Boltzmann constant and the spectral electrical conductivity, respectively [10, 11, 12]. The spectral conductivity  $\sigma$  is connected with the electronic density of states (DOS) in the vicinity of the Fermi level [13]. Thus, the low temperature behaviors of  $\rho$  and  $S$ , mentioned above, indicate the resemblance between the feature of DOS around the Fermi level in  $\text{EuNi}(\text{Si}_{0.8}\text{Ge}_{0.2})_3$  at  $P = 1.8$  GPa and that in  $\text{EuNi}(\text{Si}_{0.9}\text{Ge}_{0.1})_3$  at ambient pressure.

Figure 3 shows the pressure dependences of the magnetic transition temperatures of  $T_N$  and  $T_C$ , obtained from  $\rho(T)$  and  $S(T)$  curves of  $\text{EuNi}(\text{Si}_{0.8}\text{Ge}_{0.2})_3$ , in the form of  $\ln T_N$  ( $\ln T_C$ ) vs.  $P$ . As shown in Fig 3, both  $T_N$  and  $T_C$  increase linearly with increasing pressure at the rate of  $d \ln T_N / dP \approx 0.14 \text{ GPa}^{-1}$  and  $d \ln T_C / dP \approx 0.2 \text{ GPa}^{-1}$ , respectively, which are almost the same values as those of  $\text{EuNiSi}_3$ , reported previously in Ref. [5]. We reported that the magnetic transition temperatures of  $T_N$  and  $T_C$  in  $\text{EuNi}(\text{Si}_{1-x}\text{Ge}_x)_3$  system depend strongly on the change of the atomic volume  $V$  induced by the atomic substitution of Si by Ge [7]. Correspondingly, we assume that the pressure dependences of  $T_N$  and  $T_C$  of  $\text{EuNi}(\text{Si}_{0.8}\text{Ge}_{0.2})_3$  can be expressed by using the following Grüneisen parameters  $\Omega_{T_N}$  and  $\Omega_{T_C}$ , respectively,

$$\Omega_{T_N} = -\frac{d \ln T_N}{d \ln V} = \frac{1}{\kappa} \frac{d \ln T_N}{dP}, \quad (1)$$

$$\Omega_{T_C} = -\frac{d \ln T_C}{d \ln V} = \frac{1}{\kappa} \frac{d \ln T_C}{dP}. \quad (2)$$

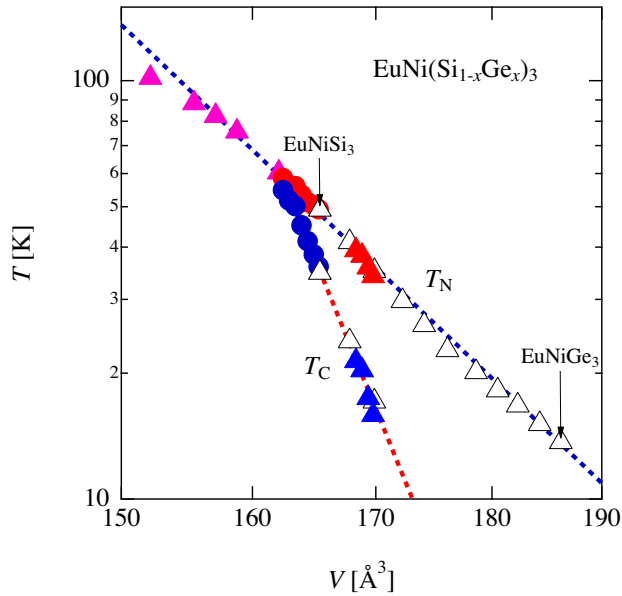


Figure 4: Atomic volume  $V$  dependences of the magnetic transition temperatures  $T_N$  and  $T_C$  of  $\text{EuNi}(\text{Si}_{1-x}\text{Ge}_x)_3$  compounds in double logarithmic scale. The pressure is transformed into the change of the atomic volume according to Eqs. (1) and (2).

Here,  $\kappa = -d \ln V / dP$  is the compressibility of  $\text{EuNi}(\text{Si}_{0.8}\text{Ge}_{0.2})_3$ . The Grüneisen parameters  $\Omega_{T_N}$  and  $\Omega_{T_C}$  can be obtained from the results of the Ge composition  $x$  dependences of  $T_N$ ,  $T_C$ , and  $V$  (the lattice parameters) [7]. Then we can determine the value of the compressibility  $\kappa$ , which is assumed as a constant for whole range of  $x$  in  $\text{EuNi}(\text{Si}_{1-x}\text{Ge}_x)_3$ . The reasonable value of the compressibility for  $\text{EuNi}(\text{Si}_{1-x}\text{Ge}_x)_3$  system,  $\kappa \approx 1.1 \times 10^{-2} \text{ GPa}^{-1}$ , was obtained by using the values of  $d \ln T_N / dP$  and  $d \ln T_C / dP$ , obtained from the line fittings to the plots of  $\ln T_N$  and  $\ln T_C$  vs.  $P$ , shown in Fig. 3. This value is consistent with that of  $\kappa \approx 1.4 \times 10^{-2} \text{ GPa}^{-1}$  for  $\text{EuPtP}$  [14] and of  $\kappa \approx 1.0 \times 10^{-2} \text{ GPa}^{-1}$  for  $\text{RCO}_2$  (R: rare earths) system [15], for example.

The plots of  $T_N$  and  $T_C$  against the atomic volume  $V$  in double logarithmic scale are shown in Fig. 4. The results of the pressure measurements for the compounds with  $x = 0$  and  $0.2$  are also indicated by solid symbols, where the pressure  $P$  is transformed into the change of the atomic volume according to Eqs. (1) and (2). The plots of  $T_N$  and  $T_C$  vs.  $V$  in double logarithmic scale lie on the individual dashed straight line, as shown in Fig. 4, revealing the validity of Eqs. (1) and (2). It is found that the effect of the increase of Si concentration on  $T_N$  and  $T_C$  is the same as that of the application of high pressure, resulting in an increase of  $T_N$  and  $T_C$ . These results indicate that the change of the atomic volume due to the atomic replacement or the applying pressure is responsible for the changes of the magnetic transition temperatures  $T_N$  and  $T_C$ . From the plots of  $T_N$  and  $T_C$  against  $V$  in Fig. 4, it is reasonable to consider that  $T_C$  and  $T_N$  merge together at  $V_c \approx 162 \text{ \AA}^3$ , and only the antiferromagnetic phase transition, instead of the ferromagnetic one [6], was observed in the region below  $V_c$ . Further study is necessary to clarify the magnetic state of  $\text{EuNiSi}_3$  under high pressure.

In summary, we have measured the electrical resistivity and thermopower of  $\text{EuNi}(\text{Si}_{0.8}\text{Ge}_{0.2})_3$ , which is a compound near to the phase boundary between the ferromagnetic and antiferro-

magnetic in the phase diagram for  $\text{EuNi}(\text{Si}_{1-x}\text{Ge}_x)_3$  system, under pressures up to 1.8 GPa at temperatures from 2 to 300 K. The magnetic transition temperatures  $T_N$  and  $T_C$  of  $\text{EuNi}(\text{Si}_{0.8}\text{Ge}_{0.2})_3$  increase with increasing pressure. The pressure dependences of  $T_N$  and  $T_C$  are expressed by the Grüneisen parameters, which means that the changes of  $T_N$  and  $T_C$  of  $\text{EuNi}(\text{Si}_{1-x}\text{Ge}_x)_3$  system are strongly connected with the change of the atomic volume induced by the applying pressure or the atomic substitution. We obtained the reasonable value of the compressibility,  $\kappa = 1.1 \times 10^{-2} \text{ GPa}^{-1}$ , for  $\text{EuNi}(\text{Si}_{1-x}\text{Ge}_x)_3$  system by using the Grüneisen parameters for  $T_N$  and  $T_C$ .

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